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PPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
10/026,020	12/27/2001	Ralph H: Johnson	ph H: Johnson V637-02670 US		
128 75	90 12/19/2003		EXAMINER		
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101 COLUMBI		ART UNIT	PAPER NUMBER		
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MORRISTOW	N. NJ 07962-2245	2828			

DATE MAILED: 12/19/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

è		Application No.		Applicant(s)	<u> </u>				
. 5		10/026,020	20 JOHNSON, RALPH H.		н Н.				
•	Office Action Summary	Examin r		Art Unit					
		Dung (Michael) T N		2828	AW_				
Period fo	The MAILING DATE of this communication app	pears on the cover s	he t with the c	orrespondence add	iress'				
A SH THE I - Exte after	ORTENED STATUTORY PERIOD FOR REPL MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communications. Precing for reply specified above is less than thirty (30) days, a reply	136(a). In no event, howeve	er, may a reply be tim	ely filed	mmunication				
- Failu - Anyı earne	b) period for reply is specified above, the maximum statutory period for to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailined patent term adjustment. See 37 CFR 1.704(b).	e, cause the application to b	ecome ABANDONEI) (35 U.S.C. § 133).	minumeason.				
Status 1) 🛣	Responsive to communication(s) filed on 4/7	<u>16</u> 3							
2a)□		action is non-final.							
3)[3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Disposit	ion of Claims	•							
4)🖂	Claim(s) 1-28 and 45-59 is/are pending in the	application.							
	4a) Of the above claim(s) is/are withdraw	n from consideration	on.	Ω)				
5)	Claim(s) is/are allowed.			Paul I	φ				
6)🖂	0) \(\sigma\) \(\dagger\) \(\d								
7)	Claim(s) is/are objected to.		2:10	PAUL IP	~\/AA444E				
8)□	Claim(s) are subject to restriction and/o	or election requirem	ent.	ervisory patent Echnology cente					
Applicat	ion Papers		•						
	The specification is objected to by the Examine								
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.									
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).									
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).									
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.									
Priority (under 35 U.S.C. §§ 119 and 120								
a)	Acknowledgment is made of a claim for foreig All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Burea See the attached detailed Office action for a list	ts have been received ts have been received ts have been received the documents have the control of the certified copers.	red. red in Applicati e been receive a)). ies not receive	on No ed in this National S					
s 3 a 14)⊟ A	Acknowledgment is made of a claim for domest ince a specific reference was included in the fir 7 CFR 1.78. a) The translation of the foreign language processes the company of the foreign language processes the company of the first sentence of the foreign was included in the first sentence of the company of of the co	est sentence of the solution ovisional application its priority under 35	specification or n has been rec U.S.C. §§ 120	in an Application leived. and/or 121 since	Data Sheet. a specific				
Attachmen	ıt(s)	_	•						
2) Notic	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449) Paper No(s) <u>&</u>	5) 🔲 N	otice of Informal P	(PTO-413) Paper No(s atent Application (PTO					

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DETAILED ACTION

Response to Arguments

Applicant's arguments with respect to claims 1-28 and 45-59 have been considered but are most in view of the new ground(s) of rejection.

Double Patenting

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970); and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

Claims 1-28 and 45-59 are provisionally rejected under the judicially created doctrine of obviousness-type double patenting over claims 1-16 and 19-59 of copending Application No. 10/026044, claims 1-6 of copending Application No. 10/026055 and claims 1-27 and 29-34 of copending Application No. 10/026016.

This is a provisional obviousness-type double patenting rejection.

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The subject matter claimed in the instant application is fully disclosed in the referenced copending application and would be covered by any patent granted on that copending application since the referenced copending application and the instant application are claiming common subject matter, as follows: Claims 1, 45 and 53 of application number 10/026020 recite a VCSEL comprising at least one quantum well having a depth of at least 40 meV and comprised of InGaAsSb. Claims 1, 37 and 48 of copending application number 10/026044 recite a VCSEL comprising at least one quantum well having a depth of at least 40 meV and comprised of GaAsSb. Further claim 48 of copending application number 10/026044 recites an AlGaAs confinement layers sandwiching said barrier layers. The limitation in claims 1, 45 and 53 of this. application is basically the same as the limitation in claims 1, 37 and 48 of the copending application 10/026044. The claims recite alternative substitution elements such as Al, In, N with the basic material GaAs. Therefore claims 1-28 and 45-59, and claims 1-16 and 19-59 of copending application 10/026044 are considered as the "same invention". Furthermore, the substituted elements are disclosed in each application specification and title of the invention. Thus, the claims are not patentable distinct from each other.

The subject matter claimed in the instant application is fully disclosed in the referenced copending application and would be covered by any patent granted on that copending application since the referenced copending application and the instant application are claiming common subject matter, as follows: Claims 1, 45 and 53 of application number 10/026020 recite a VCSEL comprising at least one quantum well having a depth of at least 40 meV and comprised of InGaAsSb. Claims 1, 3 and 5 of copending application number 10/026055 recite a VCSEL comprising at least one quantum well having a depth of at least 40 meV and comprised of

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InGaAs; AlGaAs and GaAsN confinement layers. The limitation in claims 1, 45 and 53 of this application is basically the same as the limitation in claims 1, 3 and 5 of the copending application 10/026055. The claims recite alternative substitution elements such as Al, In, N with the basic material GaAs. Therefore claims 1-28 and 45-53 and claims 1-6 of copending application 10/026055 are considered as the "same invention". Furthermore, the substituted elements are disclosed in each application specification and title of the invention. Thus, the claims are not patentable distinct from each other.

The subject matter claimed in the instant application is fully disclosed in the referenced copending application and would be covered by any patent granted on that copending application since the referenced copending application and the instant application are claiming common subject matter, as follows: Claims 1, 45 and 53 of application number 10/026020 recite a VCSEL comprising at least one quantum well having a depth of at least 40 meV and comprised of InGaAsSb. Claims 1, 25 and 33 of copending application number 10/026016 recite a VCSEL comprising at least one quantum well having a depth of at least 40 meV and comprised of InGaAsSbN. Further claim 25 of copending application number 10/026016 recites an AlGaAs confinement layers. The limitation in claims 1, 45 and 53 of this application is basically the same as the limitation in claims 1, 25 and 33 of the copending application 10/026016. The claims recite alternative substitution elements such as Al, In, N, Sb with the basic material GaAs. Therefore claims 1-28 and 45-59 and claims 1-27 and 29-34 of copending application 10/026016 are considered as the "same invention". Furthermore, the substituted elements are disclosed in each application specification and title of the invention. Thus, the claims are not patentable distinct from each other.

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Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-28 and 45-59 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jewell et al (US6359920) in view of Ishikawa (US5841152).

With respect to claims 1-28 and 45-59, Jewell et al disclose a VCSEL (100) comprising an active region (110) further comprising at least one quantum well (126, 128) of GaAsSb having a depth of 40meV (Fig.2b) and further including GaAs barrier layer (54') sandwiching said at least one quantum well and GaAs confinement layer (70') sandwiching said active region and nitrogen to be used at least 1% in group V of semiconductor material in the active region.

Jewell also disclose alternative substitution elements such as In, Al, N, Sb with the basic material GaAs and the quantum well is up to and including 50 ´, note col. 5 line 24 to col. 37 line 18, see figures 1-11. However, Jewell do not disclose the quantum well depth is defined as the difference between a valence band offset and a conduction band offset. Ishikawa teaches the quantum well depth is defined as the difference between a valence band offset and a conduction band offset (col.5, 1.13-15). For the benefit of calculating the quantum well depth, it would have been obvious to one having ordinary skill in the art at the time the invention was made to provide

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Jewell the quantum well depth is defined as the difference between a valence band offset and a conduction band offset as taught by Ishikawa.

Communication Information

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dung (Michael) T Nguyen whose telephone number is (703) 305-7159. The examiner can normally be reached on 8:30 - 17:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Paul Ip can be reached on (703) 308-3098. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 306-3329.

Nguyen (Michael) Dung

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